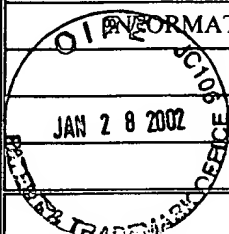

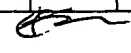


U.S. Department of Commerce, Patent and Trademark Office				Atty Docket No.		Serial No.		
				M-9455 US		09/670,000		
<div style="text-align: center;">  </div>				Applicants				
				James M. Holden et al.				
				Filing Date		Group		
				September 25, 2000		2878		
U.S. Patent Documents								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA							
	AB							
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	AE							
	AF							
	AG							
	AH							
	AI							
	AJ							
	AK							
Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
	AL							
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
	AQ	Raymond, C. et al., "Scatterometry for the measurement of metal features" <i>Proceedings of SPIE Vol. 2998</i> (2000) Pages 135-146.						
	AR							
	AS							
Examiner 			Date Considered <u>9/13/02</u>					
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.</p>								

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicants	
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		Filing Date	Group
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	AH						
	AI						
	AJ						
	AK						

Foreign Patent Documents

							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
	AL							
	AM							
	AN							
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>[Signature]</i>	AQ	Bischoff, J. et al., "Modeling of optical scatterometry with finite-number-of-periods gratings" <i>SPIE</i> , Vol. 3743, Pages 41-48.
<i>[Signature]</i>	AR	Bischoff, J. et al., "Single feature metrology by means of light scatter analysis" <i>SPIE</i> Vol. 3050, Pages 574-585.
<i>[Signature]</i>	AS	Kong, W. et al., "A Hybrid Analysis of Ellipsometry Data from Patterned Structures", <i>Characterization and Metrology for ULSI Technology: 2000 International Conference</i> , Pages 373-377 (2001).

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT						Applicants			
(Use several sheets if necessary)						James M. Holden et al.			
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						September 25, 2000		2878	
U.S. Patent Documents									
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate		
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								Translation	
		Document	Date	Country	Class	Subclass	Yes	No	
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<i>[initials]</i>	AM	Raymond, C. et al., "Resist and etched line profile characterization using scatterometry" <i>SPIE</i> Vol. 3050 (1977) 476-486.							
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